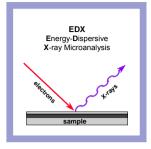
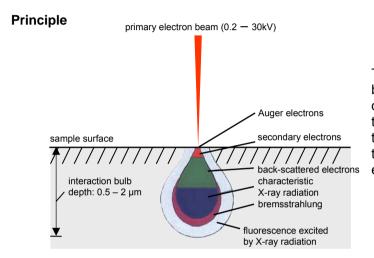


Energy Dispersive X-ray Microanalysis



The primary electron beam generated in the electron microscope is not only a valuable tool for imaging the surface but also for analysing the chemical composition of samples. The electron beam interacts with the sample within a volume which depends on the acceleration voltage of the electron beam and on the elemental composition of the sample. As a result, x-ray radiation is produced, along with secondary electrons (SE) and other radiation. The energy of the x-ray radiation depends on the atomic number of the respective emitting atom and is therefore characteristic for that element. The EDX detector registers the emitted x-ray radiation and sorts it into an energetic spectrum.



The x-ray radiation is excited within a spherical or bulb-shaped volume (see figure). The penetration depth of the electrons and the emission depth of the x-rays depends on the acceleration voltage for the electrons, the mass density of the sample, and the energy of the x-ray radiation. The depth of the excitation volume ranges from < 1 μ m to a few μ m.

Detector:
Energy resolution:
Elemental detection:

Si(Li) detector (liquid-nitrogen-cooled) \leq 129 eV for Mn K α atomic numbers \geq 4 (Be)

Options

Measurement and qualitative/quantitative evaluation of EDX spectra at surface points or areas. Determination of the elemental distribution along a line (line-scan) or over an area (mapping).

Requirements

Specifications

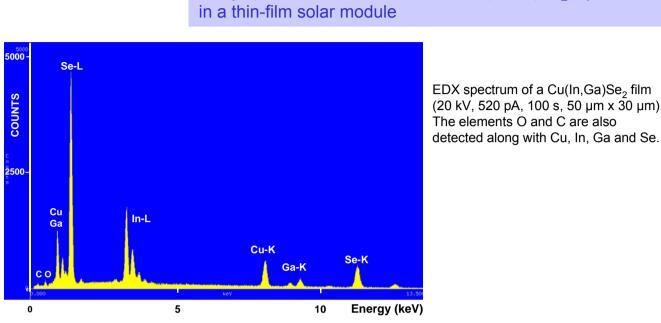
Sample size: Sample thickness: Sample properties: up to 50 mm x 50 mm up to 30 mm dry, no out-gassing, vacuum-compatible



EDX Application Examples

Using the energy dispersive x-ray microanalysis system integrated with our HR-SEM, we can examine the evaporated, sputtered, or chemically deposited films or layer systems for thin-film solar modules regarding their chemical composition or analyse defects which occurred during the coating process.

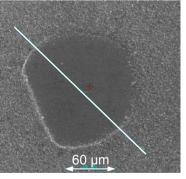
X-ray spectrum of the solar-active Cu(In,Ga)Se₂ layer



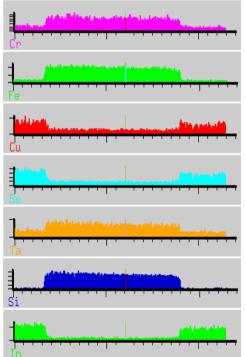
EDX spectrum of a Cu(In,Ga)Se₂ film (20 kV, 520 pA, 100 s, 50 µm x 30 µm). The elements O and C are also

Distribution of elements from a line-scan over a coating defect in a Cu(In,Ga)Se₂ film on a Cr steel substrate

Left: Scanning electron microscopic image of a circular defect. Right: Line-scan diagonal over the circular defect (line in the left image). The concentrations of the elements Cu, In and Se are much lower within the defect, whereas the elements Fe and Cr from the steel substrate and Ta and Si from an intermediate layer are more strongly represented.



Interpretation: The Cu(In,Ga)Se₂ film is almost completely absent within the defect. The excitation volume of the electron beam therefore penetrates the underlying layers down to the steel substrate and the elements from these layers are more strongly represented in the measurement. The absence of the absorber film likely resulted from a foreign particle which was on the substrate during Cu(In,Ga)Se₂ growth.



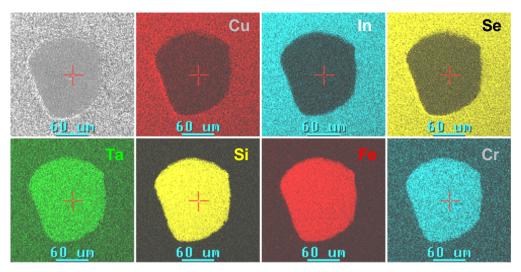
Dr. Theresa Friedlmeier Industriestrasse 6, 70565 Stuttgart, Germany Tel.: ++49 (0)711 - 7870-293, Fax.: ++49 (0)711 - 7870-230 E-Mail: theresa.friedlmeier@zsw-bw.de Internet: www.zsw-bw.de

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EDX Application Examples

Elemental distribution images (mappings) of a coating defect from a Cu(In,Ga)Se₂ film on a Cr steel substrate



SEM image of a circular defect (upper left) and elemental distribution images for the elements Cu, In, Se, Ta, Si, Fe, and Cr at the defect. The concentrations of the elements Cu, In and Se are much lower within the defect (darker), whereas the signals from the elements Fe and Cr from the steel substrate and Ta and Si from an intermediate layer are stronger.

Interpretation: The Cu(In,Ga)Se₂ film is almost completely absent within the defect. The excitation volume of the electron beam therefore penetrates the underlying layers down to the steel substrate and the elements from these layers are more strongly represented in the measurement. The absence of the absorber film likely resulted from a foreign particle which was on the substrate during Cu(In,Ga)Se₂ growth.



